

Technical Note:

Items listed in 7002.1.a. through h. are included in this Item only if all surfaces of any of the Items coming in direct contact with the chemical(s) being processed or contained are made from any of the following materials:

1. Nickel or alloys with more than 40% nickel by weight;
2. Alloys with more than 25% nickel and 20% chromium by weight;
3. Fluoropolymers;
4. Glass or glass-lined (including vitrified or enameled coating);
5. Graphite (applies only to heat exchangers, condensers, distillation and absorption columns, multi-walled piping and pumps);
6. Tantalum or tantalum alloys;
7. Titanium or titanium alloys;
8. Zirconium or zirconium alloys;
9. Ceramics (applies only to pumps)
10. Ferrosilicon (applies only to pumps).
11. Silicon carbide (applies only to heat exchanges and condensers); or
12. Titanium carbide (applies only to heat exchanges and condensers)

2. Remotely operated filling equipment.

Technical Note:

Items are considered to be included only if all surfaces that come in direct contact with the chemical(s) being processed or contained are made from any of the following materials:

- a. Nickel or alloys with more than 40% nickel by weight; or
- b. Alloys with more than 25% nickel and 20% chromium by weight.

3. Incinerators designed to destroy CW agents, controlled precursors or chemical munitions, possessing all of the following characteristics:

- a. Specially designed waste supply systems;
- b. Special handling facilities; **and**
- c. Average combustion chamber temperature greater than 1000°C;

Technical Note:

Items listed in 7002.3.a. through c. are considered to be included only if all surfaces in the waste supply system that come into direct contact with the waste products are made from or lined with any of the following materials:

1. Nickel or alloys with more than 40% nickel by weight;
2. Alloys with more than 25% nickel and 20% chromium by weight; or
3. Ceramics.

4. Toxic gas monitoring systems and dedicated detectors:

- a. Designed for continuous operation and useable for the detection of CW agents, AG-controlled precursors or organic compounds containing phosphorus, sulfur, fluorine or chlorine at concentrations of less than 0.3 mg/m³; or
- b. Designed for the detection of cholinesterase-inhibiting activity.

Note:

Governments may permit the shipment of equipment (identified in Item 7002.) which is specially designed for use in civil applications such as food processing, pulp and paper processing, or water purification and is, by the nature of its design, inappropriate for use in storing, processing, producing or conducting and controlling the flow of chemical weapon agents or any of the precursors chemicals which are included in item 7004.

(Item 7002. applies to all destinations **except** Argentina, Australia, Austria, Belgium, Czech Republic, Denmark, Finland, France, Germany, Greece, Hungary, Iceland, Ireland, Italy, Japan, Republic of Korea, Luxembourg, Netherlands, New Zealand, Norway, Poland, Portugal, Romania, Slovak Republic, Spain, Sweden, Switzerland, United Kingdom and United States.)

7003. CWC Materials

1. CWC Schedule 1 A Toxic Chemicals:

- a. **O-Alkyl** (equal to or less than C₁₀, including cycloalkyl) alkyl (Methyl, Ethyl, n-Propyl or Isopropyl) - phosphonofluoridate; e.g. **Sarin** (GB):O-Isopropyl methylphosphono-fluoridate, (CAS 107-44-8); **Soman** (GD):O-Pinacolyl methylphosphono-fluoridate, (CAS 96-64-0);
- b. **O-Alkyl** (equal to or less than C₁₀, including cycloalkyl) N,N-dialkyl (Methyl, Ethyl, n-Propyl or Isopropyl) phosphoramidocyanidates, e.g., Tabun: O-Ethyl N,N-dimethylphosphoramidocyanidate, (CAS 77-81-6);
- c. **O-Alkyl** (H or equal to or less than C₁₀, including cycloalkyl) S-2-dialkyl (Methyl, Ethyl, n-Propyl or Isopropyl)-aminoethyl alkyl (Methyl, Ethyl, n-Propyl or Isopropyl) phosphonothiolates and corresponding alkylated or protonated salts, e.g., VX: O-Ethyl S-2-diisopropylaminoethyl methylphosphonothiolate, (CAS 50782-69-9);
- d. **Sulphur mustards:**
2-Chloroethylchloromethylsulphide, (CAS 2625-76-5); Mustard gas: Bis(2-chloroethyl) sulphide, (CAS 505-60-2); Bis(2-chloroethylthio) methane, (CAS 63869-13-6); Sesquimustard: 1,2-Bis (2-chloroethylthio) ethane, (CAS 3563-36-8); 1,3-Bis (2-chloroethylthio) -n-propane, (CAS 63905-10-2); 1,4-Bis (2-chloroethylthio) -n-butane, (CAS 142868-93-7); 1,5-Bis(2-chloroethylthio) -n-pentane, (CAS 142868-94-8); Bis (2-chloroethylthiomethyl) ether; (CAS 63918-90-1); O-Mustard: Bis (2-chloroethylthioethyl) ether, (CAS 63918-89-8);
- e. **Lewisites:**
Lewisite 1: 2-chlorovinylchloroarsine, (CAS 541-25-3); Lewisite 2: Bis (2-chlorovinyl) chloroarsine, (CAS 40334-69-8); Lewisite 3: Tris (2-chlorovinyl) arsine, (CAS 40334-70-1);
- f. **Nitrogen mustards:**
HN1: bis (2-chloroethyl) ethylamine, (CAS 538-07-8); HN2: bis (2-chloroethyl) methylamine, (CAS 51-75-2); HN3: tris (2-chloroethyl) amine, (CAS 555-77-1);
- g. **Saxitoxin**, (CAS 35523-89-8);
- h. **Ricin**, (CAS 9009-86-3).

2. CWC Schedule 1 B Precursors

- a. Alkyl(Me, Et, n-Pr or i-Pr)phosphonyldifluorides e.g., DF: Methylphosphonyldifluoride, (CAS 676-99-3);
- b. O-Alkyl (H equal to or less than C₁₀, including cycloalkyl) O-2-dialkyl (Me, Et, n-Pr or i-Pr)-aminoethyl alkyl (Me, Et, n-Pr or i-Pr) phosphonites and corresponding alkylated or protonated salts; e.g., QL: O-Ethyl O-2-diisopropylamino ethyl methylphosphonite, (CAS 57856-11-8);
- c. Chlorosarin: O-Isopropyl methylphosphonochloridate, (CAS 1445-76-7);
- d. Chlorosoman: O-Pinacolyl methylphosphonochloridate, (CAS 7040-57-5).